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## Abstract:

In the catalytic field, the combination of Au and TiO<sub>2</sub> plays an important role due to an extraordinary high activity for low-temperature catalytic combustion, partial oxidation of hydrocarbons, hydrogenation of unsaturated hydrocarbons, and reduction of nitrogen oxides and so on. We have deposited Au film of 2 nm thickness on the surface of TiO<sub>2</sub> substrate by physical vapor deposition (PVD) Technique using Ultra High Vacuum (UHV) chamber at a pressure of  $2 \times 10^{-7}$  Torr. Au has been uniformly deposited on the TiO<sub>2</sub> surface although island structures were observed by investigating the AFM and SEM images along with the EDX spectrum and mapping. The electronic structure from the interface of Au and TiO<sub>2</sub> has been observed by the Scanning Tunneling Spectroscopy (STS). We found that when the size of the Au particle is more than 4 nm, it shows metallic nature. However, when the size of the Au particle is around 2 nm, it shows semiconducting nature.

